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(54) **MEMBRANE PROBE WITH ANCHORED ELEMENTS**

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(51) **Int. Cl.**⁷ **H01R 12/00**

(52) **U.S. Cl.** **439/67**

(58) **Field of Search** 439/67, 66, 91; 174/264, 265, 266

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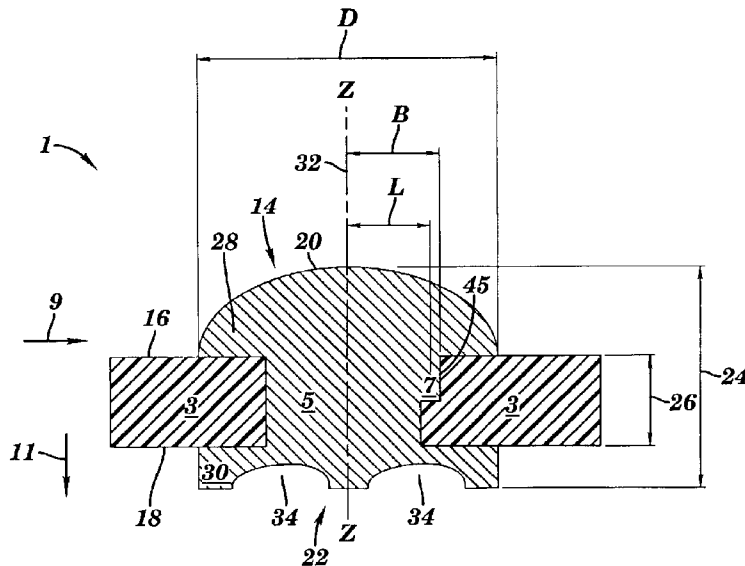
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(57) **ABSTRACT**

A structure and method to establish an electrical connection between a tester and an electrical component. A flexible dielectric layer has a first side and a second side. A through via extends through the first side and the second side of the dielectric layer. A blind via is placed in a position that is offset from the through via and extends laterally in a first direction from a section of the first through via to a section of the flexible dielectric layer. The blind via extends in a second direction from the first side of the flexible dielectric layer to a section of the flexible dielectric layer that is between the first side and the second side of the dielectric layer. An electrically conductive member extends through the through via and extends into the blind via, thereby filling the through via and the blind via. The electrically conductive member has a first surface and a second surface. Any distance between the first surface and the second surface is greater than a distance between the first side of the dielectric layer and the second side of the dielectric layer.

18 Claims, 6 Drawing Sheets



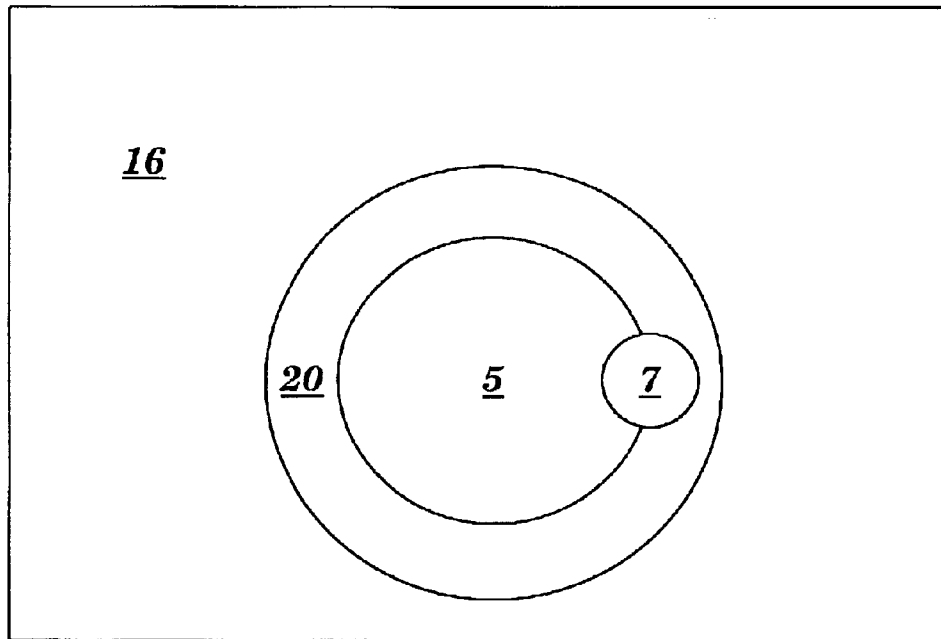


FIG. 2

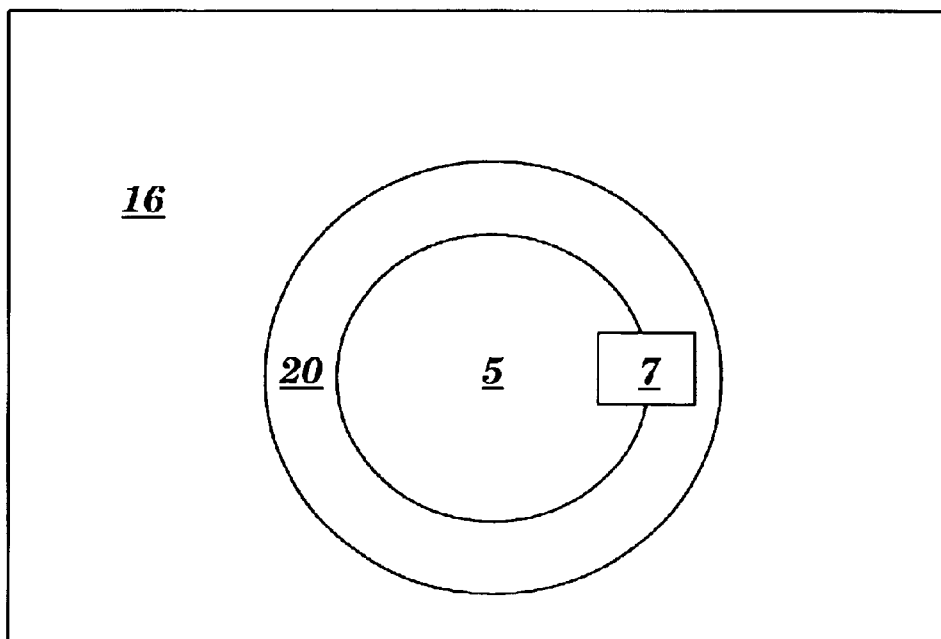


FIG. 3

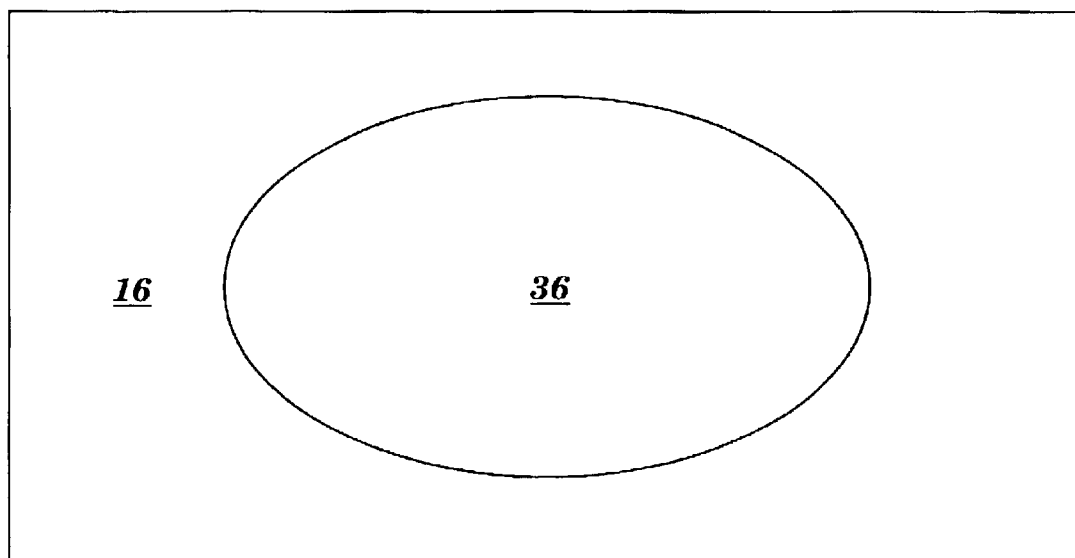


FIG. 4

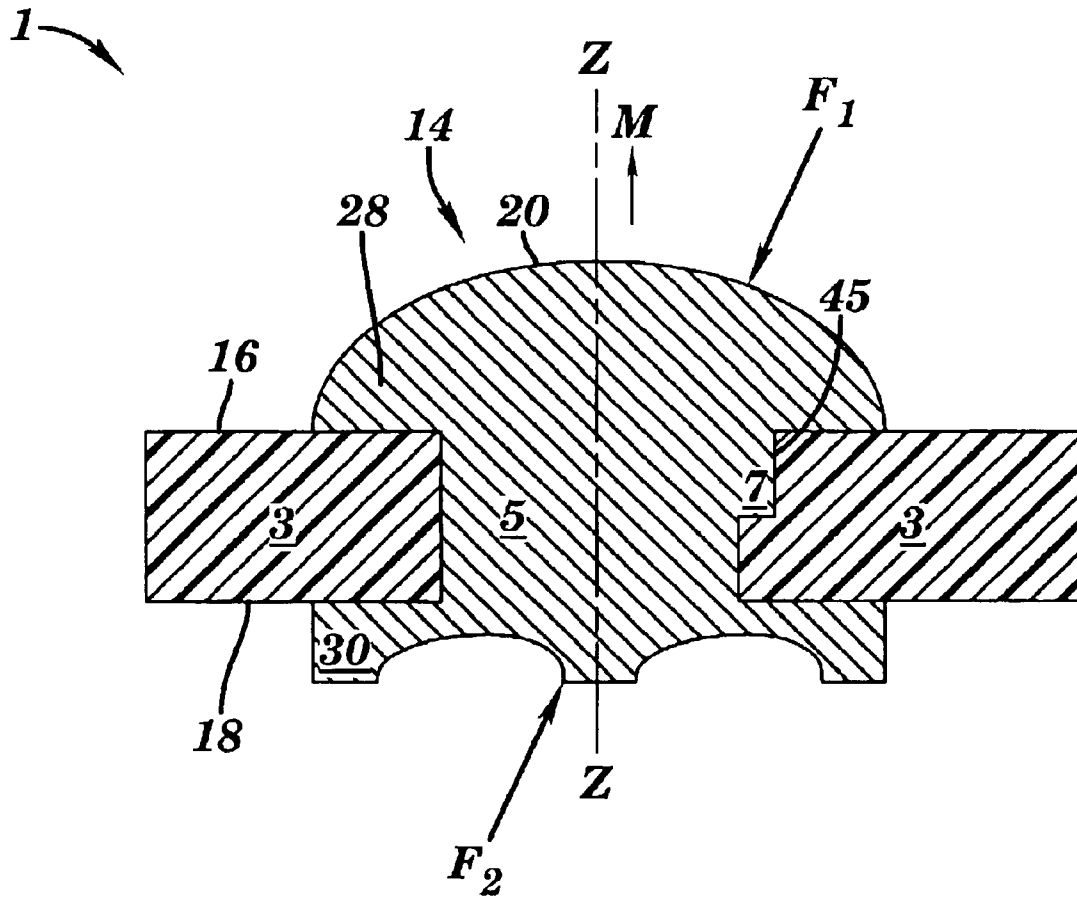


FIG. 5

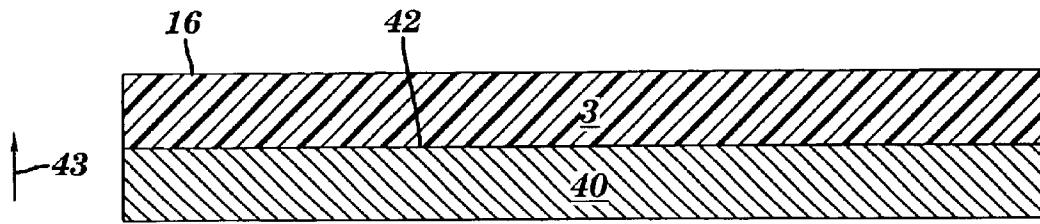


FIG. 6A

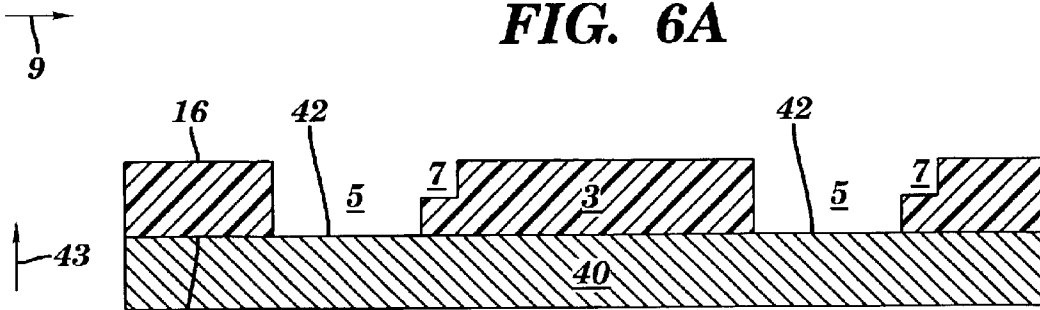


FIG. 6B

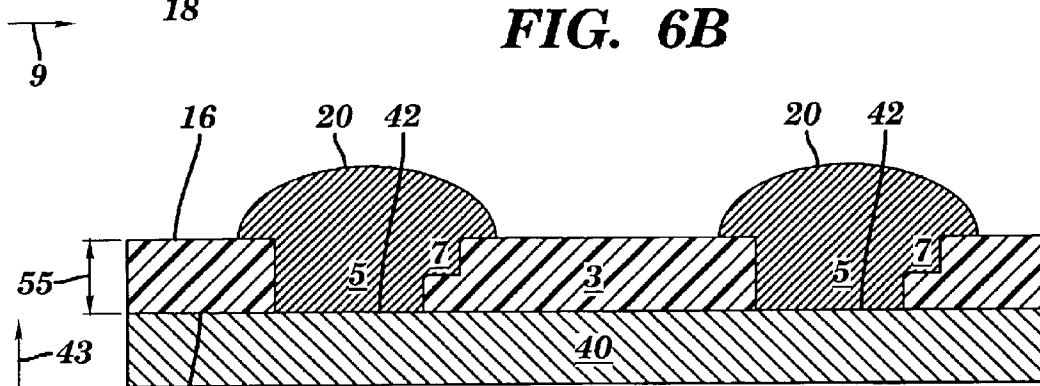


FIG. 6C

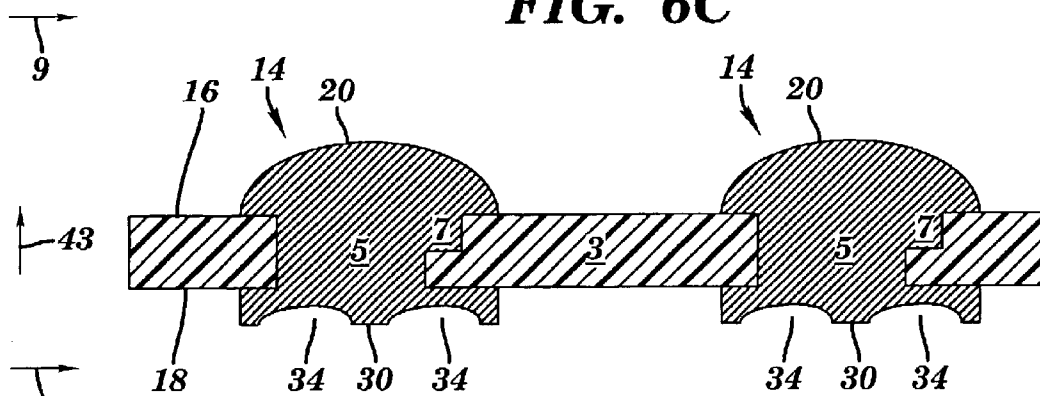


FIG. 6D

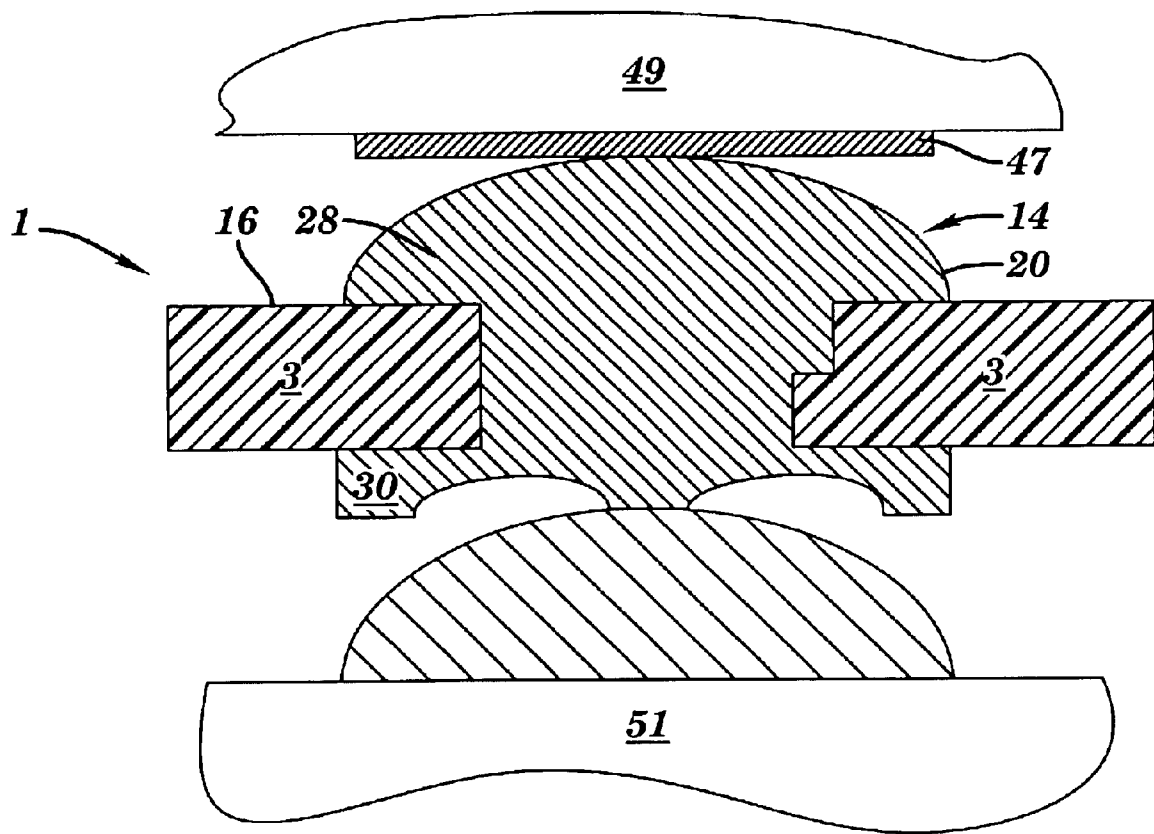


FIG. 7

MEMBRANE PROBE WITH ANCHORED ELEMENTS

BACKGROUND OF THE INVENTION

1. Technical Field

The present invention relates to a probe used to establish an electrical connection between a test device and an electrical component.

2. Related Art

Probes used for establishing an electrical connection between a test device and an electrical component may consist of electrically conductive rivets within a dielectric material. These rivets are typically placed in a via within the dielectric material. When a force is applied to the rivet from the test device and the electrical component, the rivet may tend to spin within the via causing the rivet to electrically short to an adjacent via, thereby causing the electrical component to fail. Thus there is a need for preventing such failure.

SUMMARY OF THE INVENTION

The present invention provides an electrical interconnection structure, comprising:

a flexible dielectric layer having a first side and a second side;

a first through via extending through the first side and the second side of the dielectric layer;

a first blind via, wherein the first blind via is offset from the first through via and extends laterally in a first direction from a section of the first through via to a section of the flexible dielectric layer, and wherein the first blind via extends in a second direction from the first side of the flexible dielectric layer to a section of the flexible dielectric layer that is between the first side and the second side of the dielectric layer; and

a first electrically conductive member extending through the first through via and extending into the first blind via, wherein the first electrically conductive member has a first surface and a second surface, and wherein any distance between the first surface and the second surface is greater than a distance between the first side of the dielectric layer and the second side of the dielectric layer.

The present invention provides an electrical interconnection structure, comprising:

a flexible dielectric layer having a first side and a second side;

a non-circular through via extending through the first side and the second side of the dielectric layer; and

an electrically conductive member extending through the through via, wherein the electrically conductive member has a first surface and a second surface, wherein a distance between the first surface and the second surface is greater than a distance between the first side of the dielectric layer and the second side of the dielectric layer.

The present invention provides a method for forming an electrical interconnection structure, comprising:

providing a flexible dielectric layer having a first side and a second side;

coupling a first side of a metallic layer to the second side of the flexible dielectric layer;

creating a first through via extending from the first side and the second side of the dielectric layer;

creating a first blind via offset from the first through via and extending laterally from the first through via in a first direction and extending in a second direction from the first side of the flexible dielectric layer to a section of the flexible dielectric layer that is between the first side and the second side of the dielectric layer;

forming a first bump by electroplating a metallic material on to the first side of the metallic layer and within the first through via, wherein the metallic material is over-plated in a third direction, filling the first through via, the first blind via, and extending in the third direction so that any distance between a first surface of the first bump and the first side of the metallic layer is greater than a distance between the first side and the second side of the dielectric layer, and wherein due to the over-plating the metallic material extends laterally in the first direction and extends laterally in a direction that is opposite to the first direction; and

etching a first pad at the end of the metallic layer, wherein the pad is electrically coupled to the bump, and wherein a first electrically conductive member is formed from the first bump, the filled first through via, the filled first blind via, and the etched first pad.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 illustrates a front cross sectional view of an electrical interconnection structure comprising an electrically conductive member and a circular blind via, in accordance with embodiments of the present invention.

FIG. 2 illustrates a top view of the electrical interconnection structure of FIG. 1, in accordance with embodiments of the present invention.

FIG. 3 illustrates FIG. 2 with the circular blind via replaced by a rectangular blind via, in accordance with embodiments of the present invention.

FIG. 4 illustrates FIG. 2 with a non-circular through via and without a blind via, in accordance with embodiments of the present invention.

FIG. 5 illustrates FIG. 1 showing a moment about a Z—Z axis that passes through the electrically conductive member, in accordance with embodiments of the present invention.

FIGS. 6A–6D illustrate a front cross sectional view of method steps used to create the electrical interconnection structure of FIG. 1, in accordance with embodiments of the present invention.

FIG. 7 illustrates FIG. 1 with the electrically conductive member electrically coupling a test apparatus to an electrical component, in accordance with embodiments of the present invention.

DETAILED DESCRIPTION OF THE INVENTION

FIG. 1 illustrates a front cross sectional view of an electrical interconnection structure 1 comprising an electrically conductive member 14 having a first surface 20 and a second surface 22 extending through a first side 16 and a second side 18 of a flexible dielectric layer 3 to establish an electrical and mechanical connection between devices to be tested and a tester, in accordance with embodiments of the present invention. The electrical interconnection structure 1 may be a thin flexible interposer (TFI) membrane probe used for electrical testing of chips in a wafer format. The flexible dielectric layer 3 may be a polyimide (e.g., KAPTON®, etc). The flexible dielectric layer 3 may have a thickness in a range of about 0.5–2 mils. The flexible dielectric layer 3 comprises a through via 5 and a blind via 7. The via 5 and

a blind via 7 may each have vertical sidewalls (i.e., parallel to the direction 11) or angular sidewalls (with respect to the direction 11). The through via 5 extends through the first side 16 and the second side 18 of the dielectric layer. The blind via 7 is offset from the through via 5 and extends laterally in a first direction 9 from a section of the through via 5 to a section of the flexible dielectric layer 3. Additionally the blind via 7 extends in a second direction 11 through the first side 16 of the flexible dielectric layer 3 to a section of the flexible dielectric layer 3 that is between the first side 16 and the second side 18 of the dielectric layer 3. A portion of the electrically conductive member 14 fills the through via 5 and the blind via 7. The center of the blind via 7 should be offset laterally in the first direction 9 from the center of the through via 5 by an offset distance L. A first distance D is defined as a lateral extent of the first surface 20 of the electrically conductive member 14 in the direction 9 (i.e., the first distance (D) is a maximum distance across a planer region defined by an intersection of the first surface 20 of the first electrically conductive member 14 and the first side 16 of the dielectric layer 3). A second distance B is defined as a distance between a furthest edge 45 of the blind via 7 and an axis 32 that is perpendicular to the first side 16 of the dielectric layer 3 and is centrally located in the through via 5. The relationship between the aforementioned distances is as follows: $B < D/2$. The electrically conductive member 14 may be, inter alia, a rivet, etc. The electrically conductive member 14 may comprise an electrically conductive material (e.g., metal or metallic alloy) such as, inter alia, copper, nickel, aluminum, etc. The electrically conductive member 14 may be formed by a plurality of methods including, inter alia, electroplating, etc (see FIGS. 6A–6D). The through via 5 and the blind via 7 may be formed by a plurality of methods including, inter alia, mechanical or laser drilling (laser ablate). The first surface 20 of electrically conductive member 14 may be curved in shape thereby forming a curved bump 28 (i.e., if the bump 28 has a semi-spherical shape then the distance D would equal the diameter of the semispherical shape). The second surface 22 of the electrically conductive member 14 may comprise a pad 30. The pad 30 may comprise at least one recessed opening 34. A distance 24 between a top of the first surface 20 of electrically conductive member 14 and the second surface 22 of the electrically conductive member 14 is greater than a distance 26 between the first side 16 and the second side 18 of the dielectric layer. The electrically conductive member 14 may be used to establish an electrical connection between a pad 47 on a test apparatus 49 and an electrical component 51 (see FIG. 7). The test apparatus 49 may comprise, inter alia, a space transformer, etc. The electrical component 51 may comprise, inter alia, a semiconductor chip (e.g., flip chip applications), etc. The first surface 20 of the electrically conductive member 14 is electrically coupled to the pad 47 on the test apparatus 49 and the second surface 22 of the electrically conductive member 14 is electrically coupled to the electrical component 51, thereby establishing the electrical connection between a pad 47 on a test apparatus 49 and an electrical component 51. The aforementioned procedure may be used in a variety of applications. The electrical interconnect structure 1 may comprise a plurality of electrically conductive members that are equivalent to the aforementioned electrically conductive member 14 (e.g., see FIGS. 6A–6D). The plurality of electrically conductive members are electrically insulated and mechanically separated from each other.

FIG. 2 illustrates a view of a plane that is perpendicular to the axis 32 in FIG. 1 and parallel to the first side 16 of the

flexible dielectric layer 3, showing the through via 5 and the blind via 7, in accordance with embodiments of the present invention. The through via 5 and the blind via 7 in the aforementioned plane both have a circular shape. Alternatively, the through via 5 and the blind via 7 in the aforementioned plane may comprise a plurality of shapes including, inter alia, elliptical, square, rectangular, star shaped, triangular, hexagonal, etc.

FIG. 3 illustrates an alternative embodiment of FIG. 2 illustrating a view of a plane that is perpendicular to the axis 32 in FIG. 1 showing the through via 5 and the blind via 7, in accordance with embodiments of the present invention. In contrast with FIG. 2, the blind via 7 in FIG. 3 has a rectangular shape. Alternatively, the through via 5 and the blind via 7 in FIG. may comprise a plurality of shapes including, inter alia, circular, elliptical, rectangular, star shaped, triangular, hexagonal, etc.

FIG. 4 illustrates an alternative embodiment showing a view of a plane that is perpendicular to the axis 32 in FIG. 1 such that the through via 36 is non-circular in shape, in accordance with embodiments of the present invention. This embodiment comprises a non-circular through via 36 with out a blind via 7 (see FIG. 1). The non-circular through via 36 may comprise a plurality of polygonal shapes including, inter alia, circular, elliptical, square, rectangular, star shaped, triangular, hexagonal, etc. All other characteristics of the electrical interconnection structure 1 in FIG. 4 are the same as in FIG. 1.

FIG. 5 illustrates FIG. 1 showing a cross sectional view of the electrical interconnection structure 1 and showing how applied forces F_1 and F_2 may create a moment M about a Z—Z axis, in accordance with embodiments of the present invention. The forces F_1 and F_2 may or may not be parallel to each other. F_1 may be generated by from a tester 49 and F_2 may be generated from an electrical component 51 such as a semiconductor chip (see FIG. 7). Additionally, F_1 and/or F_2 may be generated from other sources such as cleaning and/or handling processes. If the blind via 7 is not present the electrically conductive member 14 may be free to rotate about the Z—Z axis within the through via 5. For example, if forces F_1 and F_2 are applied to the electrically conductive member 14, and if forces F_1 and F_2 have components in a plane that is perpendicular to the Z—Z axis, wherein said force components are displaced from the Z—Z axis, may create a moment M about the Z—Z axis. If this moment M is greater than a resistant moment created by friction between the total contact area of the electrically conductive member 14 and the total contact area of the flexible dielectric layer 3, the electrically conductive member 14 may be free to rotate about the Z—Z axis within the through via 5. The total contact area of the flexible dielectric layer 3 includes contact area under the bump 28, surface area of the through via 5, and contact area under the pad 30. If a plurality of electrically conductive members are used and the electrically conductive members are closely spaced, any rotation of the electrically conductive members may result in electrical shorting of adjacent electrically conductive members, thereby causing a short in an electrical component being tested. For example, the shape of the pads (e.g., pad 30 and adjacent pads may have a square shape) may be such that rotation of the electrically conductive members cause adjacent pads to move close to each other and touch each other. The embodiments, discussed supra in conjunction with FIGS. 1–4, of the present invention prevent such rotation of the electrically conductive member 14. Said rotation is prevented by the addition of the blind via 7 in FIGS. 1–3 which effectively creates a notch that stops

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rotation. Alternatively, said rotation is prevented by creating a non-circular through via **36** and eliminating the blind via **7** as shown in FIG. **4**, said non-circular through via **36** likewise stops rotation.

FIGS. **6A–6D** illustrate a cross sectional view of method steps used to create the electrical interconnection structure **1** of FIG. **1**, in accordance with embodiments of the present invention. In FIG. **6A**, a metallic layer **40** (e.g., copper, nickel, aluminum, etc.) is bonded to a flexible dielectric layer **3**. The metallic layer **40** may be applied by different methods including, inter alia, sputtering. The metallic layer **40** may be applied in a thickness range of about 2000–5000 angstroms. After the metallic layer **40** is deposited on the flexible dielectric layer **3** an electroplating process may be used to bring the metallic layer **40** to a full thickness (i.e., about 1 mil). In FIG. **6A**, the through via **5** is created extending from the first side **16** through the second side **18** of the dielectric layer, but not into the metallic layer **40**. The through via **5** is created by a drilling process that may include, inter alia, laser drilling. Any laser known to a person of ordinary skill in the art may be used including, inter alia, an Nd:YAG laser, etc. After the through via **5** is created, the blind via **7** is created. The blind via **7** is placed in an offset position from the through via **5**, extending laterally in a first direction **9** from the through via **5** and extending vertically in a third direction **43** from the first side **16** of the flexible dielectric layer **3** to a section of the flexible dielectric layer **3** that is between the first side **16** and the second side **18** of the dielectric layer **3**. The blind via **7** may be created by the same process as the through via **5**. The through via **5** and the blind via **7** may be created in a plurality of polygonal cross-sectional shapes including, inter alia, circular, elliptical, square, rectangular, star shaped, triangular, hexagonal, etc. If laser drilling is used, a focus on the laser may be changed to create different sized vias. An aperture may be placed in the laser beam path to create different shapes of the vias **5** and **7**. In FIG. **6C**, a curved bump **14** is formed by electroplating a metallic material (e.g., copper) on a first side **42** of the metallic layer **40** and within the through via **5**, filling the through via **5**, the blind via **7**, and extending in a direction **43**, thereby causing any distance between the first surface **20** of electrically conductive member **14** and the first side **42** of the metallic layer to be greater than a distance **55** between the first side **16** and the second side **18** of the dielectric layer. The electroplated metallic material extends laterally in the first direction **9** and extends laterally in a direction that is opposite to the first direction **9**, thereby causing the plated metallic material to plate outward over the first side **16** of the dielectric layer **3**. The surface **20** may be over plated with nickel and then gold over the nickel. Nickel forms a diffusion barrier between the copper and gold. The gold will not oxidize so that it creates very little contact resistance between the surface **20** and a tester. FIG. **6D** completes the process of forming the electrical interconnection structure **1** of FIG. **1**. The final step is to create the pad **30**. The pad **30** (e.g., sculpted pad) may be created by photolithographic and grayscale etching process. The metallic layer **40** is etched away to create a pad **30**, thereby creating the electrically conductive member **14**. The pad **30** may comprise at least one recessed curved opening **34**. This process may be repeated to form a plurality of electrically conductive members that are electrically insulated and mechanically separated each other.

FIG. **7** illustrates FIG. **1** showing a cross sectional view of the electrical interconnection structure **1** with the electrically conductive member **14** electrically coupling a test apparatus **49** to an electrical component **51**, in accordance with

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embodiments of the present invention. The electrically conductive member **14** is used to establish an electrical connection between a pad **47** on the test apparatus **49** and the electrical component **51**. The pad **47** on the test apparatus **49** may comprise, inter alia, a space transformer, etc. The electrical component **51** may comprise, inter alia, a semiconductor chip (e.g., flip chip applications), etc. A first surface **20** of the electrically conductive member **14** is electrically coupled to the pad **47** on the test apparatus **49** and a pad **30** of the electrically conductive member **14** is electrically coupled to the electrical component **51**, thereby establishing the electrical connection between a pad **47** on the test apparatus **49** and an electrical component **51**.

While there have been shown and described what are at present considered the preferred embodiments of this invention, it will be obvious to those skilled in the art that various changes and modifications can be made therein without departing from the scope of the invention as defined by the appended claims.

What is claimed is:

1. An electrical interconnection structure, comprising:
 - a flexible dielectric layer having a first side and a second side;
 - a first through via extending through the first side and the second side of the dielectric layer;
 - a first blind via, wherein the first blind via is offset from the first through via and extends laterally in a first direction from a section of the first through via to a section of the flexible dielectric layer, and wherein the first blind via extends in a second direction from the first side of the flexible dielectric layer to a section of the flexible dielectric layer that is between the first side and the second side of the dielectric layer; and
 - a first electrically conductive member extending through the first through via and extending into the first blind via, wherein the first electrically conductive member has a first surface and a second surface, and wherein any distance between the first surface and the second surface is greater than a distance between the first side of the dielectric layer and the second side of the dielectric layer.
2. The electrical interconnection structure of claim 1, further comprising:
 - a second through via extending through the first side and the second side of the dielectric layer;
 - a second blind via, wherein the second blind via is offset from the second through via and extends laterally in a first direction from a section of the second through via to a section of the flexible dielectric layer, and wherein the second blind via extends in the first direction from the first side of the flexible dielectric layer to a section of the flexible dielectric layer that is between the first side and the second side of the dielectric layer; and
 - a second electrically conductive member extending through the second through via and extending into the second blind via, wherein the second electrically conductive member has a third surface and a fourth surface, wherein a distance between the third surface and the fourth surface is greater than a distance between the first side of the dielectric layer and the second side of the dielectric layer, and wherein the second electrically conductive member is electrically insulated and mechanically separated from the first electrically conductive member.
3. The electrical interconnection structure of claim 1, wherein the first through via has a circular cross-sectional shape.

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4. The electrical interconnection structure of claim 1, wherein the first blind via has a circular cross-sectional shape.

5. The electrical interconnection structure of claim 1, wherein the first blind via has a rectangular cross-sectional shape.

6. The electrical interconnection structure of claim 1, wherein a first distance (D) is a maximum distance across a planer region defined by an intersection of the first surface of the first electrically conductive member and the first side of the dielectric layer, wherein a second distance (B) is a distance between an axis and an edge of the blind via that is furthest from the axis, wherein the axis is perpendicular to the first side of the dielectric layer, wherein the axis is centrally located in the through via, and wherein $B < D/2$.

7. The electrical interconnection structure of claim 1, wherein the first surface of the first electrically conductive member is a curved bump.

8. The electrical interconnection of structure of claim 1, wherein the second surface of the first electrically conductive member is a pad, and wherein the pad comprises at least one recessed curved opening.

9. The electrical interconnection structure or claim 1, wherein the first electrically conductive member is adapted to be electrically coupled to a test apparatus and an electrical component.

10. The electrical interconnection structure of claim 9, wherein the test apparatus comprises a space transformer, and wherein the electrical component comprises a semiconductor chip.

11. An electrical interconnection structure, comprising:
a flexible dielectric layer having a first side and a second side;
a non-circular through via extending through the first side and the second side of the dielectric layer, wherein the

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non-circular through via comprises an elliptical cross-sectional shape; and

an electrically conductive member extending through the through via, wherein the electrically conductive member has a first surface and a second surface, wherein a distance between the first surface and the second surface is greater than a distance between the first side of the dielectric layer and the second side of the dielectric layer, and wherein the first surface comprises at least one recessed curved opening.

12. The electrical interconnection structure of claim 11, wherein the electrically conductive member has a rectangular cross-sectional shape.

13. The electrical interconnection structure of claim 11, wherein the second contact surface of the electrically conductive member is a curved bump.

14. The electrical interconnection structure of claim 11, wherein the electrically conductive member is adapted to electrically couple to a test apparatus and an electrical component.

15. The electrical interconnection structure of claim 14, wherein the test apparatus comprises a space transformer, and wherein the electrical component comprises a semiconductor chip.

16. The electrical interconnection on structure of claim 11, wherein the electrical interconnection structure is a thin flexible interposer membrane probe.

17. The electrical interconnection structure of claim 11, wherein the first surface comprises a plurality of recessed curved openings.

18. The electrical interconnection structure of claim 11, wherein the at least one recessed curved opening is concave.

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